

ABSTRACT

REFLECTIVE MASK BLANK, REFLECTIVE MASK, AND MANUFACTURING
METHOD THEREFOR

The present invention pertains to a reflective mask blank (10) in which a multilayer
5 reflective film (2) that reflects EUV light and an absorption layer (3) that absorbs EUV light
are layered upon a substrate (1) in this order from the substrate (1) side, the absorption layer (3)
has a first absorption film (3a) and a second absorption film (3b) layered in this order from the
substrate side, the refractive index of the absorption layer (3) for EUV light at a wavelength of
13.5 nm is no higher than 0.95, and the first absorption film (3a) can be etched by means of
10 chemical dry etching more easily than the second absorption film (3b).

Figure 1